



ELECTRONIC PROPERTIES OF IIA HPHT DIAMOND SAMPLES FROM NEW DIAMOND TECHNOLOGY

5th ADAMAS Workshop, Darmstadt, Germany 15-16/12/2016 | Pomorski Michal

WHY TO BOTHER WITH HPHT DIAMONDS

excellent structural quality

CVD
Excellent
Diamond
Products



CVD
Element Six



HPHT 1b
lia Technology
(Singapore)



HPHT 1b
Sumitomo



HPHT 1a
New
Diamond
Technology



large size



Finished
Diamond plate



Diamond plate
on grinding holder

Affordable price

5.0 x 5.0 x 0.5 mm single-crystal mu
characteristics are listed below. You
order process.

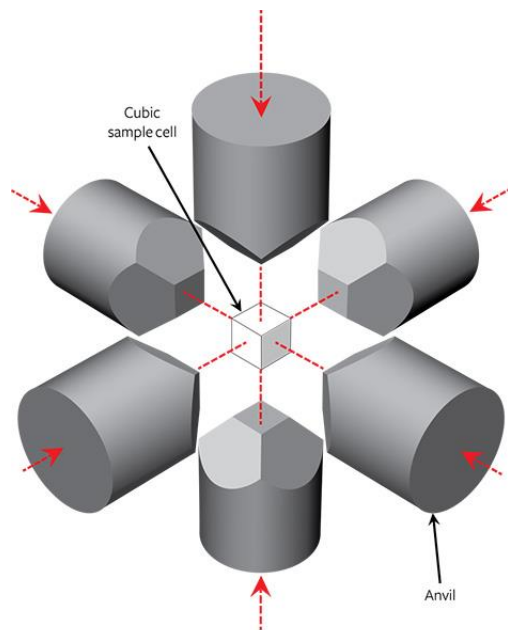
For special technical applications we
and obtain mono- or multi-sectorial

Price: 630\$

? What about electronic quality ?

1. NDT, Samples and Structural Quality
2. Current-Voltage Characteristics
3. Charge Collection Characteristics
4. TCT Characteristics
5. Summary

Multianvil cubic press



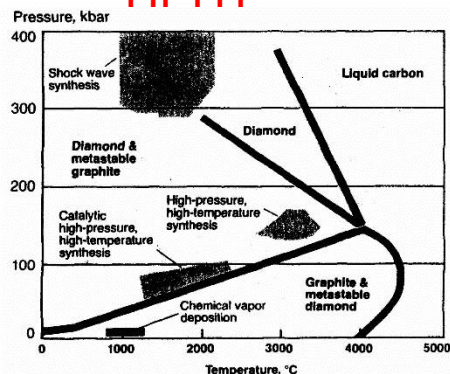
15mm



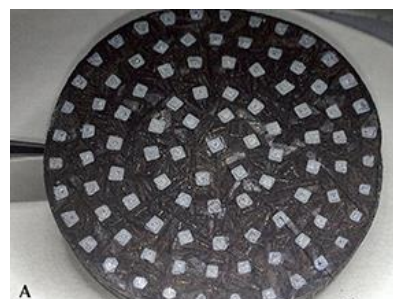
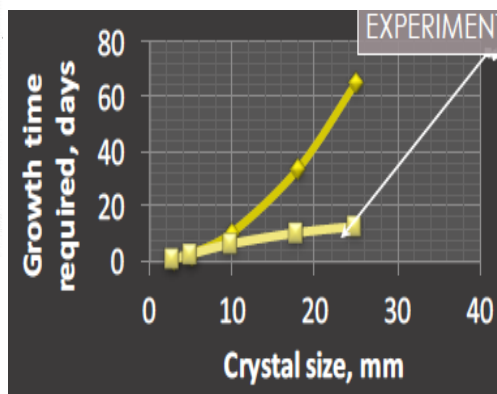
25mm

Multiseeds growth

HPHT



growth rate



Diamond cube 4x4 mm → current 200 → in three years 750

Diamond cube 7x7 mm → current 15 → in three years 60

Diamond cube 10x10 mm → current 9 → in three years 25

HPHT DIAMONDS AND NDT

<http://ndtcompany.com/>



10,02 CT



The largest in the world
Blue HPHT lab-grown diamonds:
(unveiled at JCK Show 2016)

Diamond plates have the potential which shall allow to bring electronics and optics on new level of development.

Available sizes in stock are from 3.0x3.0 mm up to 12.0x12.0 mm with standard thickness of 0.5 mm and orientation (100).

For special technical applications we can provide sizes up to 15.0x15.0 mm and vary thickness orientations, types and obtain mono- or multi-sectorial plates with different shapes.

Fore special orders you may indicate other crucial characteristics for your researches and devices



Specification

Size	5.0 x 5.0 mm
Thickness	0.5 mm
Type	Ila
Face orientation	(100)
Crystallography	Multisectorial
Edge Orientation	(110)
Roughness, Ra	≈ 5 μm
Miscut	+/-3°

Lateral Tole

Thickness T

Edges

Edge Featu

Laser Kerf:



Material properties

Boron Concentration	< 5 ppb
Nitrogen Concentration	< 5 ppb
Dislocations density	~ 10 ³ cm ⁻²
Charge Collection Efficiency	> 95%
Thermal conductivity	~ 2200 Wt/mK



SAMPLES AND STRUCTURAL QUALITY



Six HPHT diamond plates (NDT1-NDT6)

- sizes: 4 x 4 mm and ~**100 μm** thickness
- sizes: 4.5 x 4.5 mm and ~**100 μm** thickness
- $\langle 100 \rangle$, monosectoral, lia high purity
- from six different production runs

Standard procedure (used for e6 CVD) of samples metallization:

cleaning in hot acid solution $\rightarrow$ $\text{H}_2\text{SO}_4 + \text{KNO}_3$ (boiling); DI water; IPA; drying

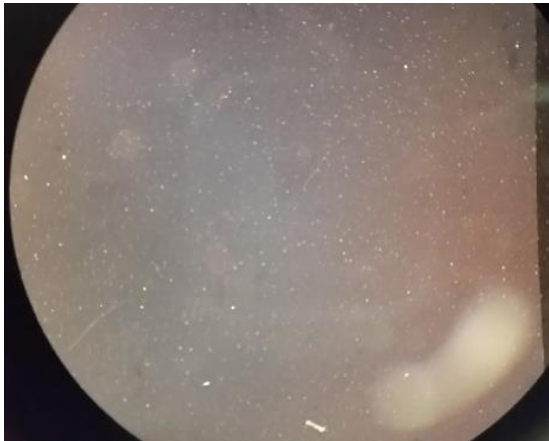
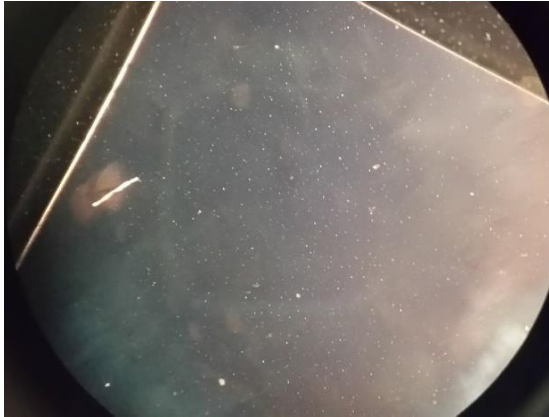
Al contacts by PVD sputtering $\rightarrow$ power 200W, bias 1000V, Argon 10-3 mbar with shadow masks, parallel plates

only two (NDT2 and NDT6) samples give promising results

SAMPLES AND STRUCTURAL QUALITY- BIREFRINGENCE

Crossed-polarizers imaging before metallization

NDT Iia HPHT



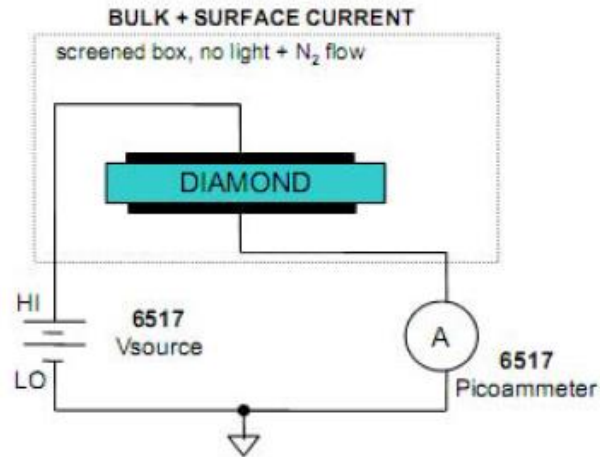
no birefringence contrast
for all six samples

E6 CVD (recently processed)



strong to moderate
biref. contrast

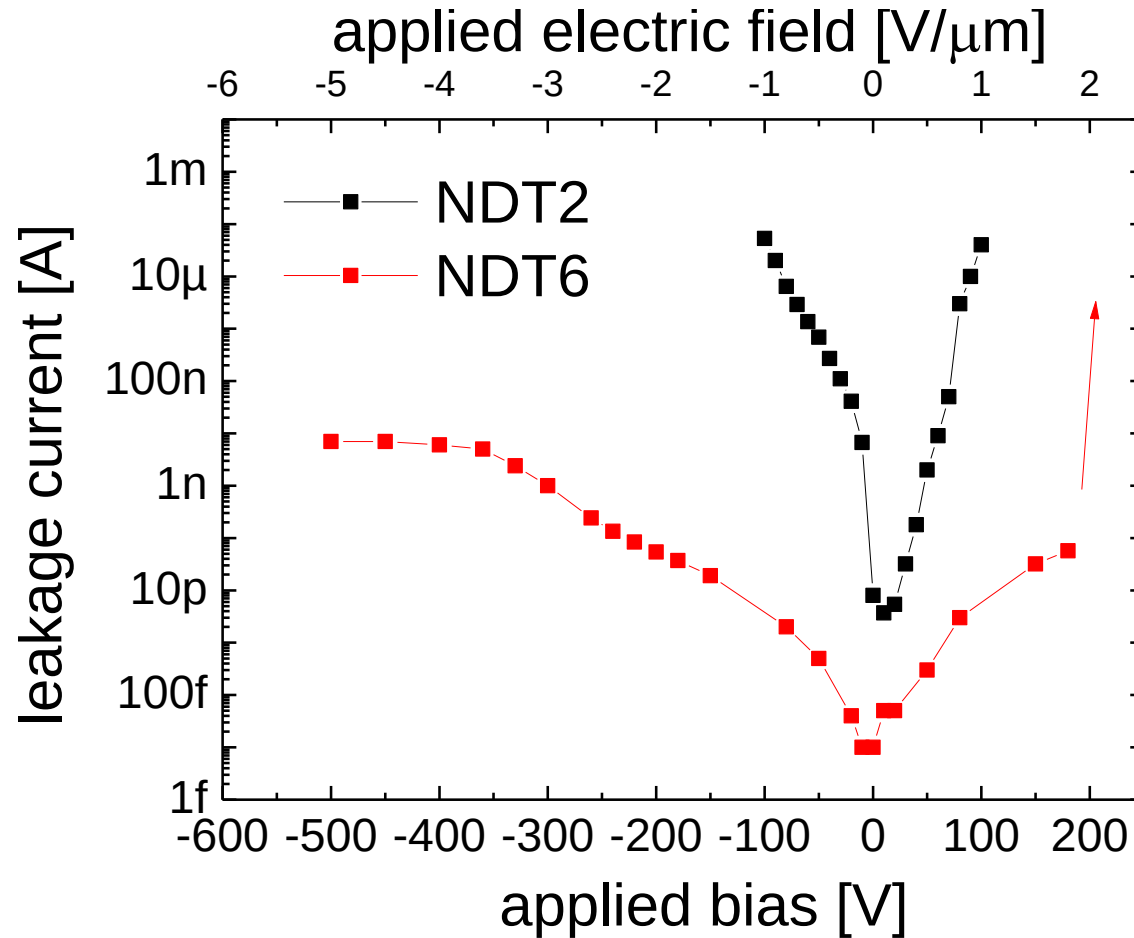
CURRENT VOLTAGE CHARACTERISTICS



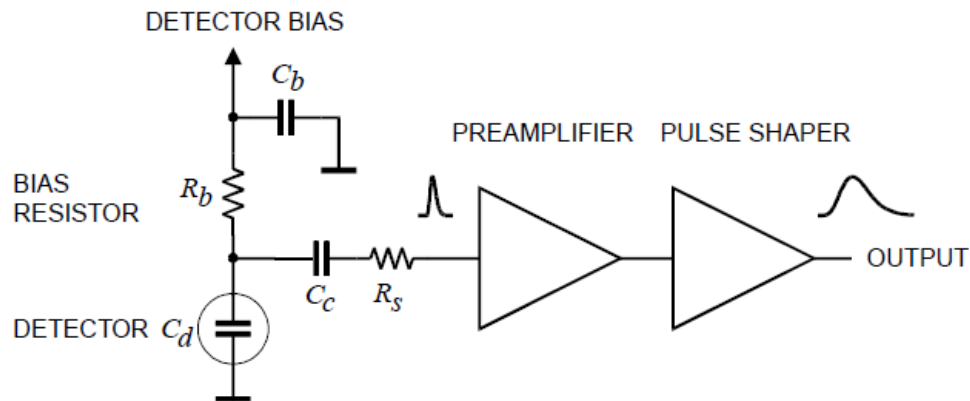
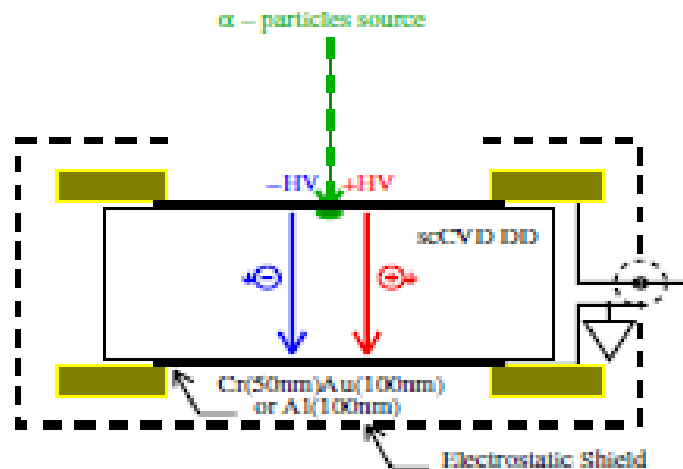
some general observations IIa HPHT for I-V @ RT (more than six samples):

- majority of the samples are not resistive, high leakage current (μA) at low bias ($0.1\text{V}/\mu\text{m}$)
- some samples are highly resistive but gives no sign of charge transport
- some samples 'leak', but give moderate to high quality charge transport properties
- one sample gives high resistivity and very good charge transport properties

CURRENT VOLTAGE CHARACTERISTICS



CHARGE COLLECTION PROPERTIES



Measurement conditions:

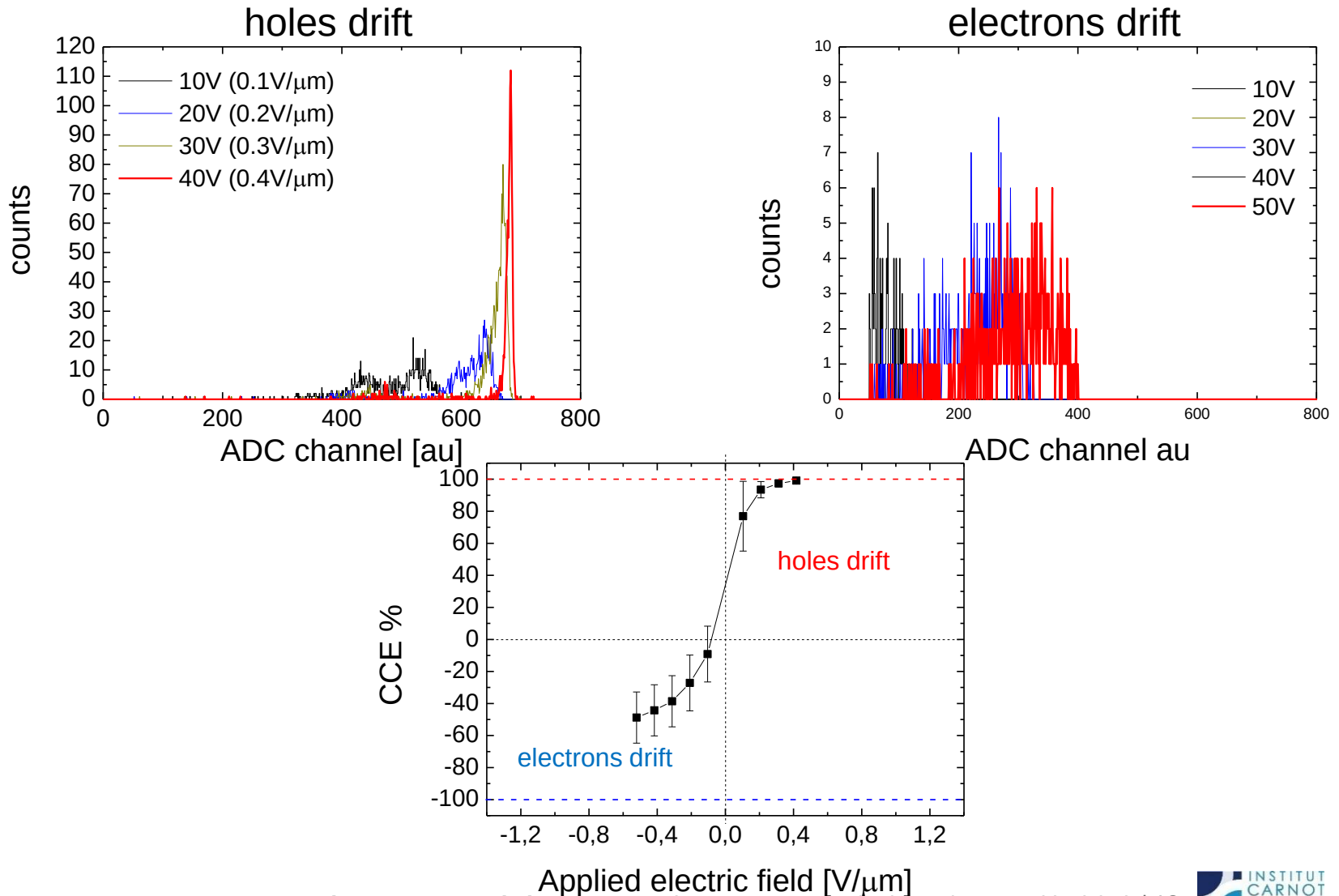
- 5.5 MeV α -particles (Am-241 source, 4kBq)
- collimated electrodes
- measurements in primary vacuum, dark
- majority of e or h drift (polarity of HV)

Set-up:

- coolFET A250 amptek preamp. (2.5 ns rise)
- 3 μ s shaping time
- pocket MCA or DSO as DAQ

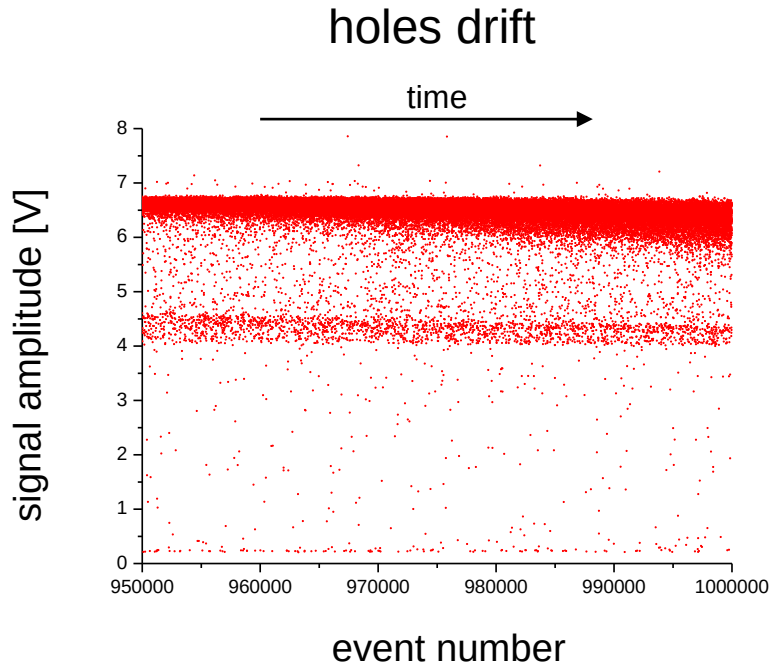
CHARGE COLLECTION PROPERTIES - NDT2

5.5 α -particles spectra vs. detector bias

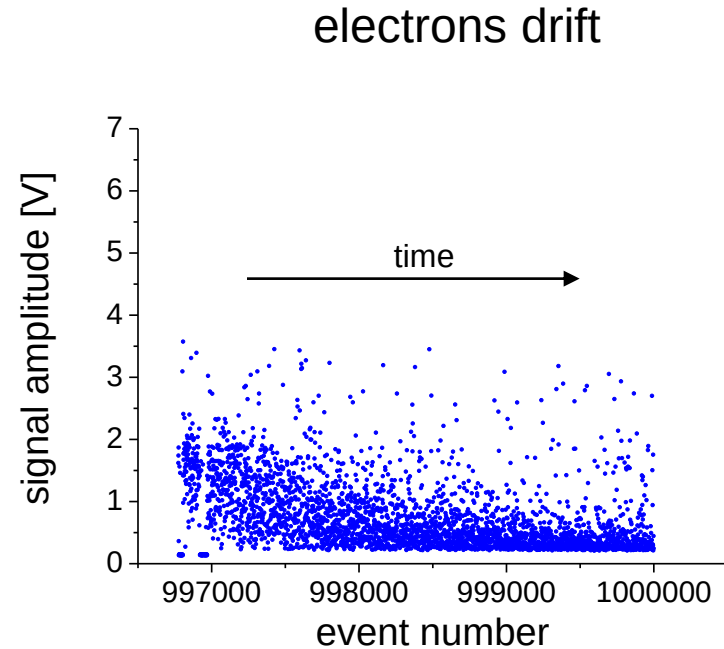


CHARGE COLLECTION PROPERTIES - NDT2

long term stability under 5.5 α -particles irradiation



weak polarization

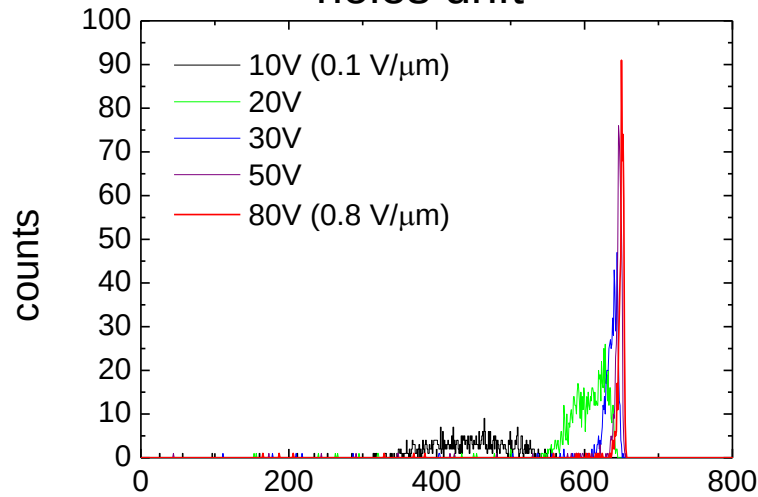


strong polarization

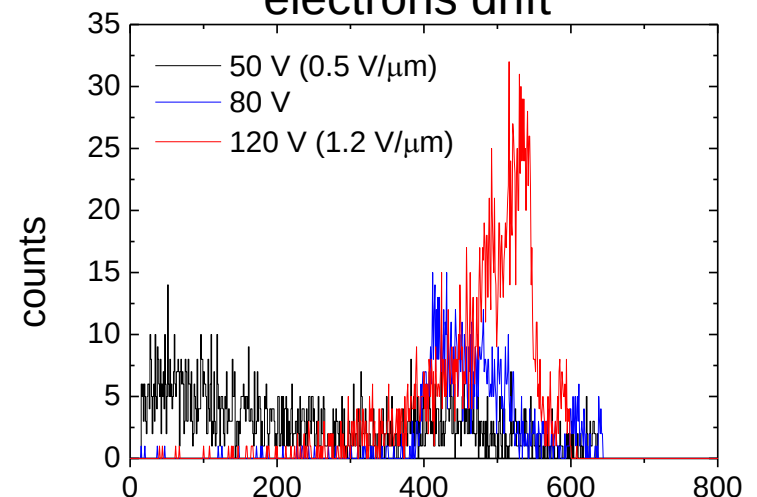
CHARGE COLLECTION PROPERTIES - NDT6

5.5 α -particles spectra vs. detector bias

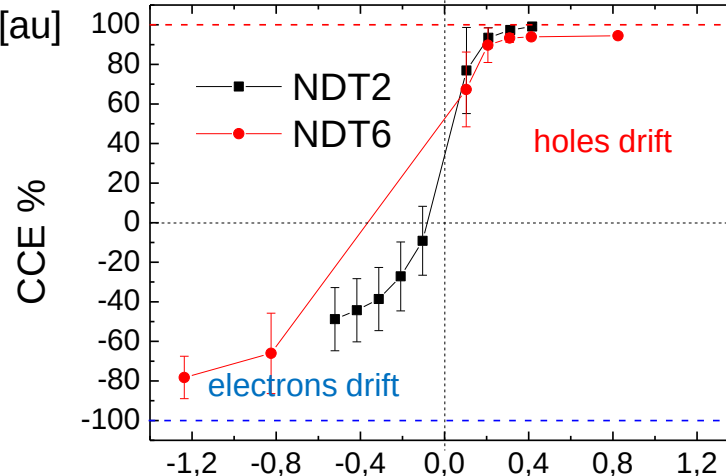
holes drift



electrons drift



ADC channel [au]

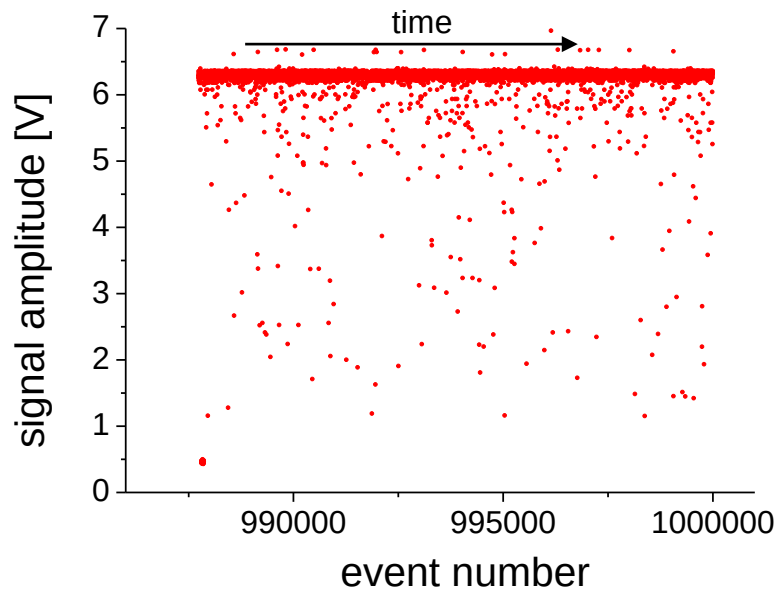


ADC channel [au]

CHARGE COLLECTION PROPERTIES - NDT6

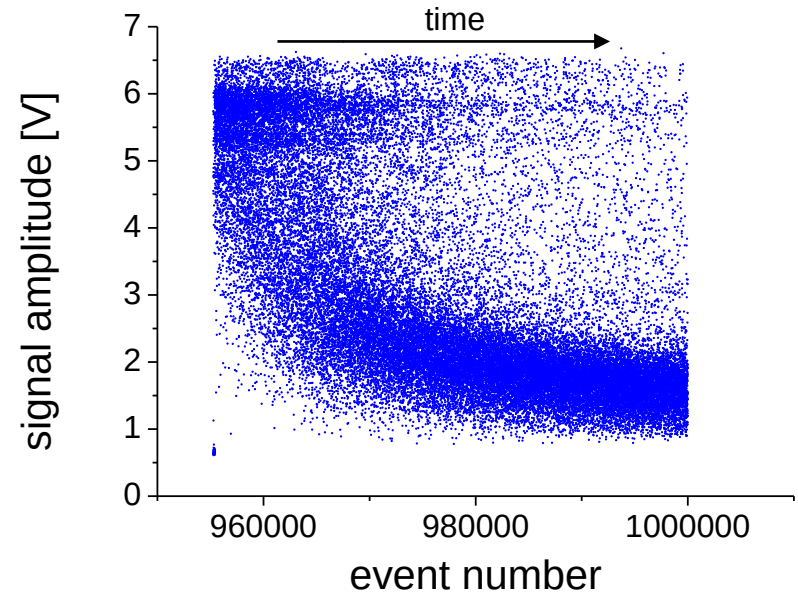
long term stability under 5.5 α -particles irradiation

holes drift



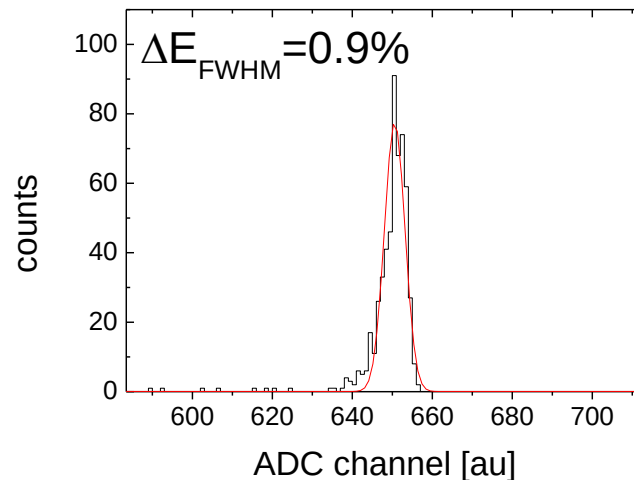
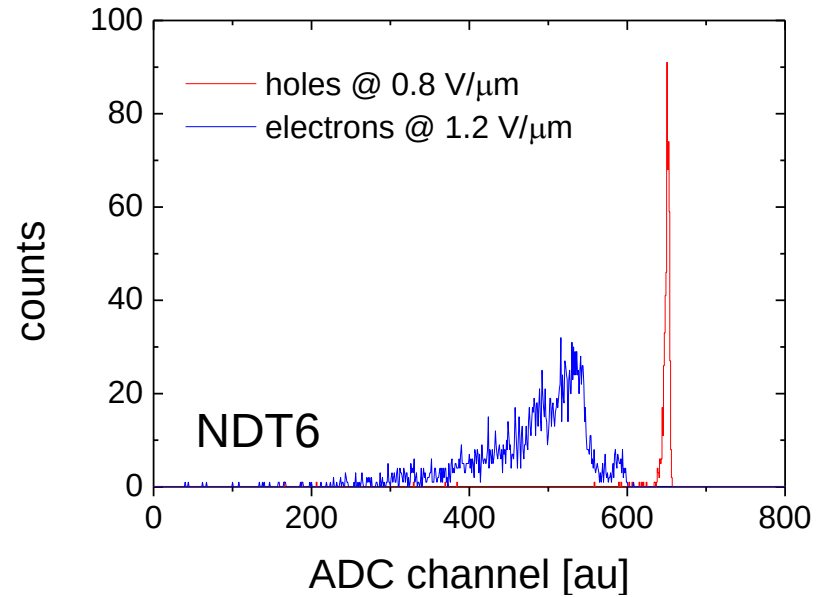
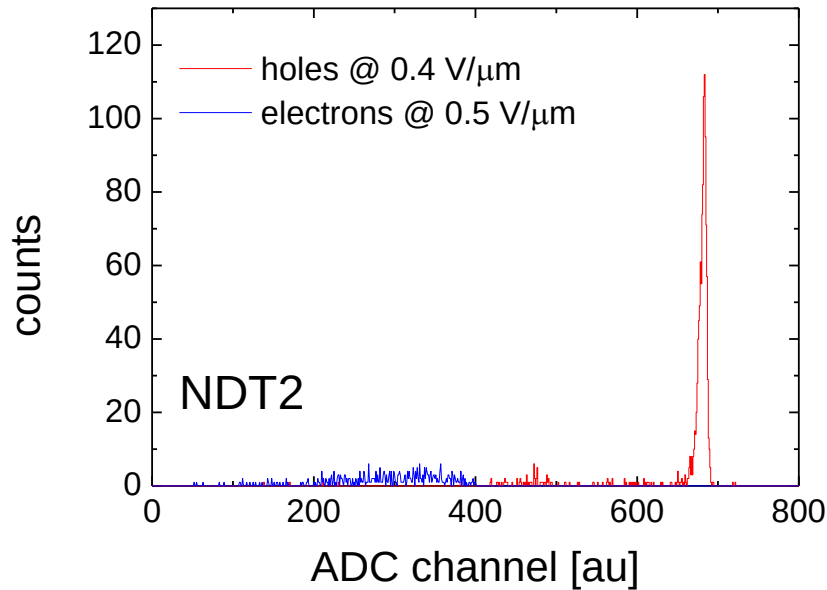
stable - no polarization

electrons drift



strong polarization

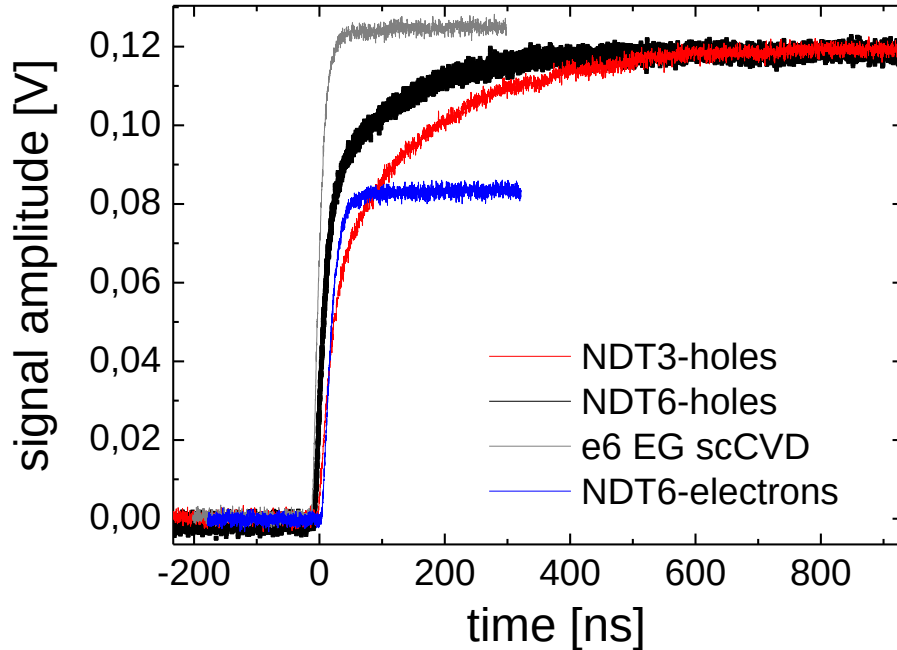
CHARGE COLLECTION PROPERTIES – BEST OF NDT2 NDT6



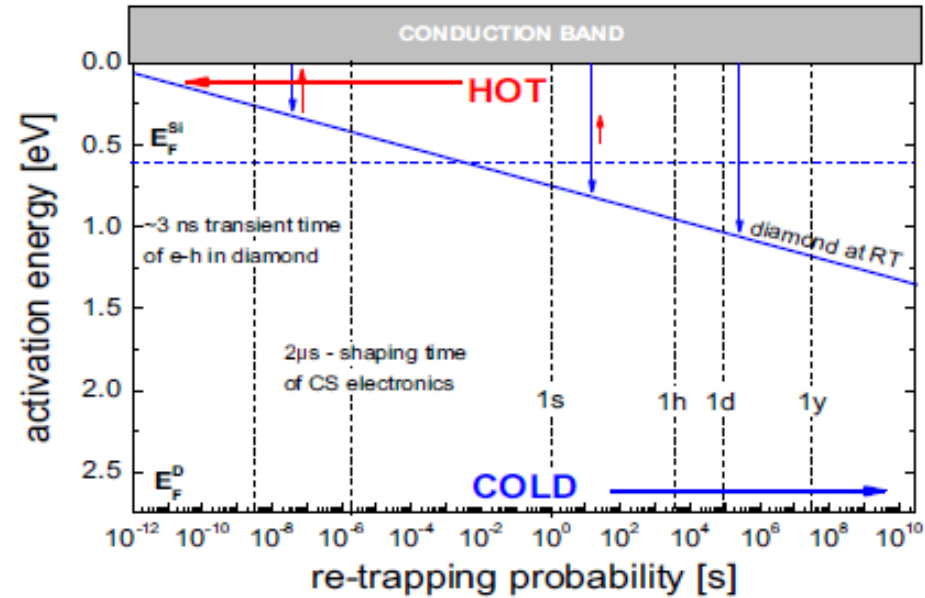
NDT6
spectroscopic grade
(holes drift)

CHARGE COLLECTION PROPERTIES

CoolFET A250 Amptek preamp

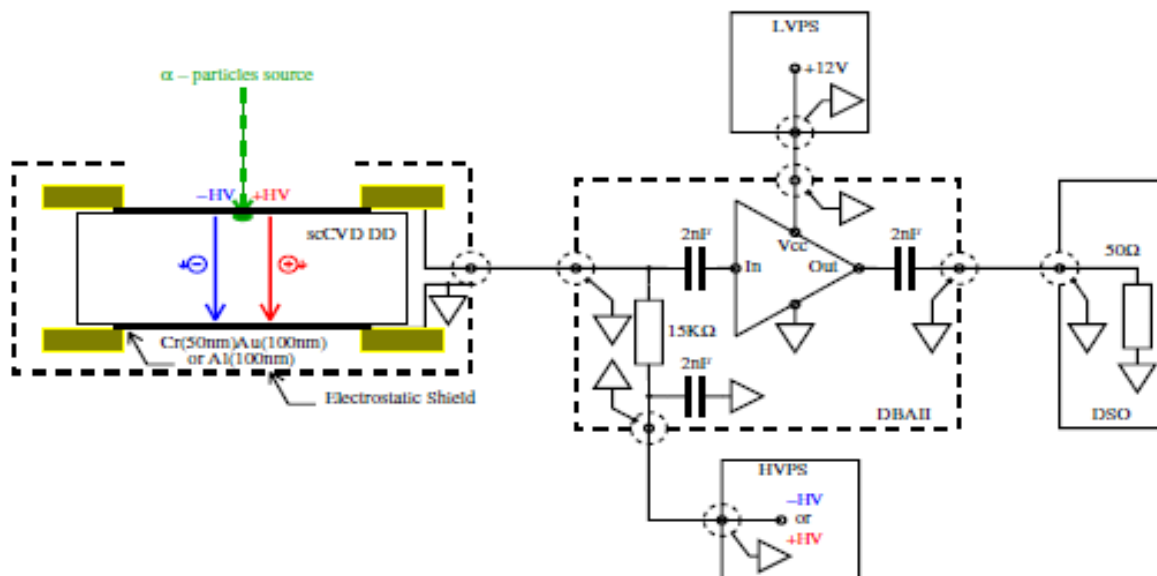


de-trapping probability @ RT



deep trapping for electrons $\rightarrow$ polarization

shallow trapping for holes $\rightarrow$ all de-trapped within 3 μ s @ RT (~ 0.3 eV)



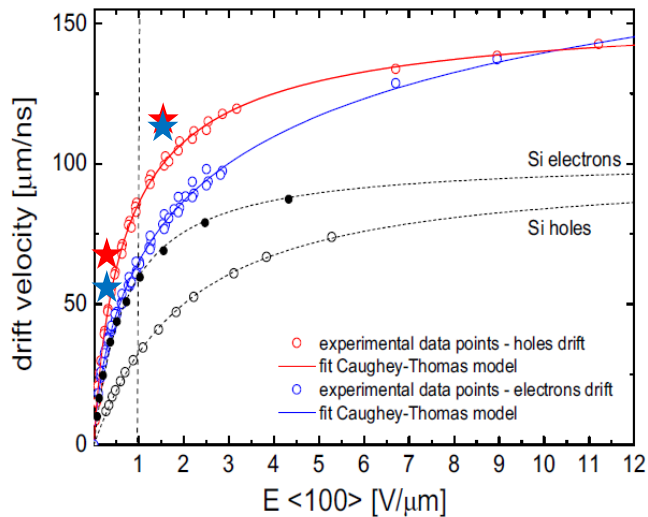
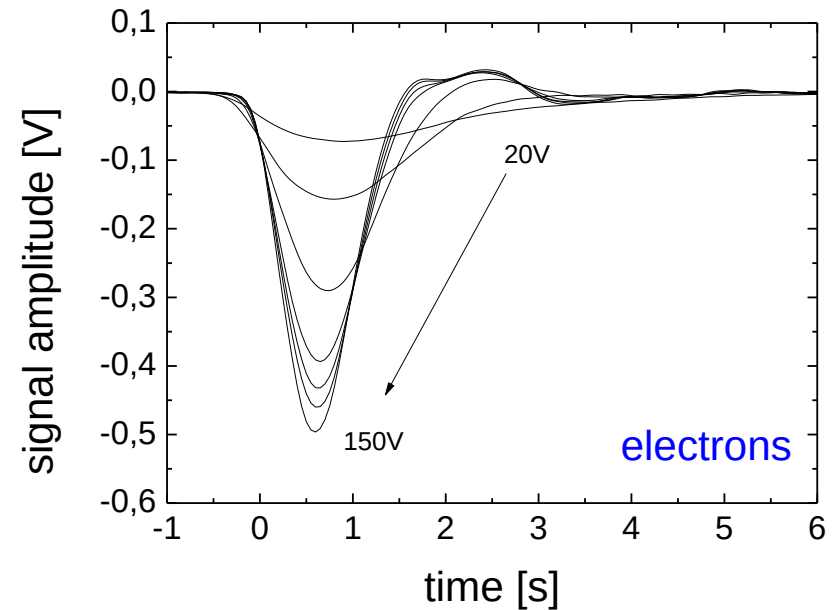
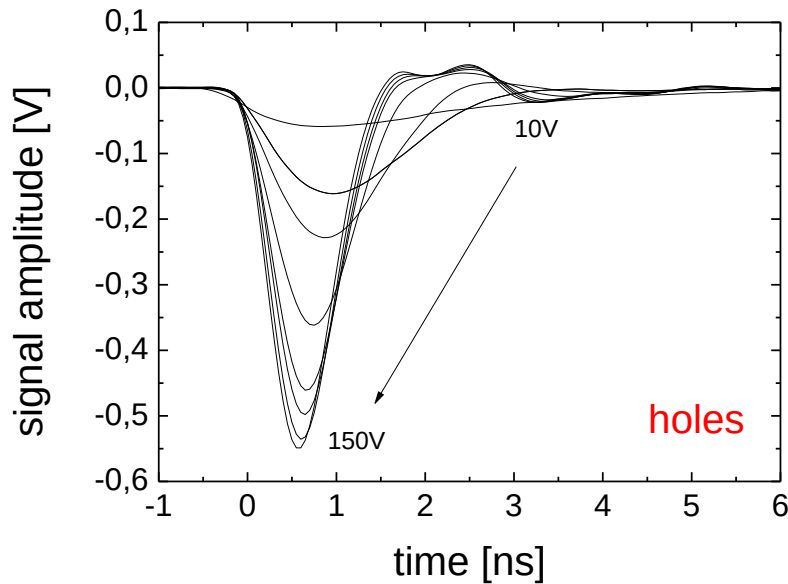
Measurements conditions:

- 5.5 MeV α -particles (Am-241 source, 4kBq)
- collimated electrodes
- measurements in primary vacuum
- majority of e or h (polarity of HV)

Set-up:

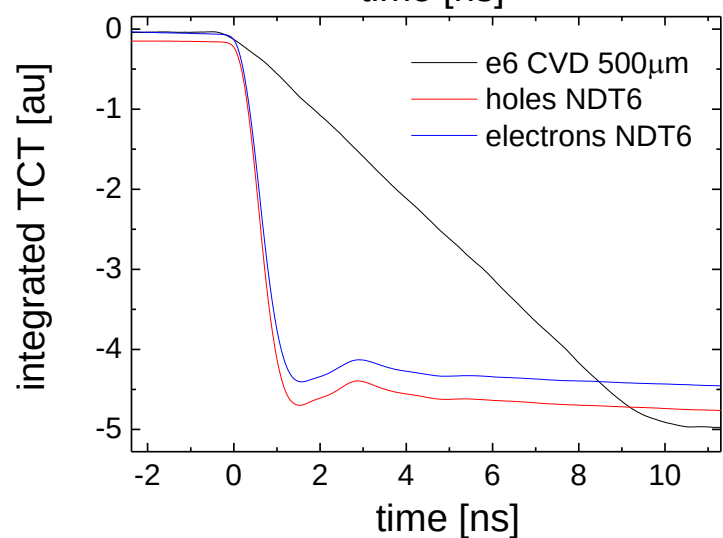
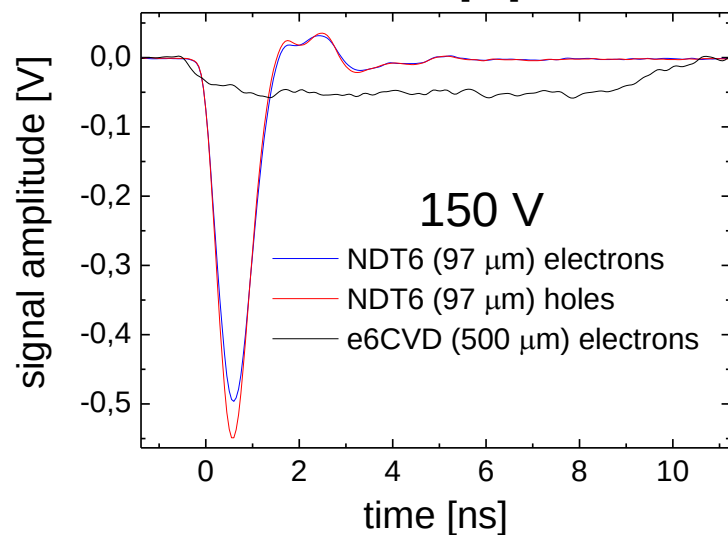
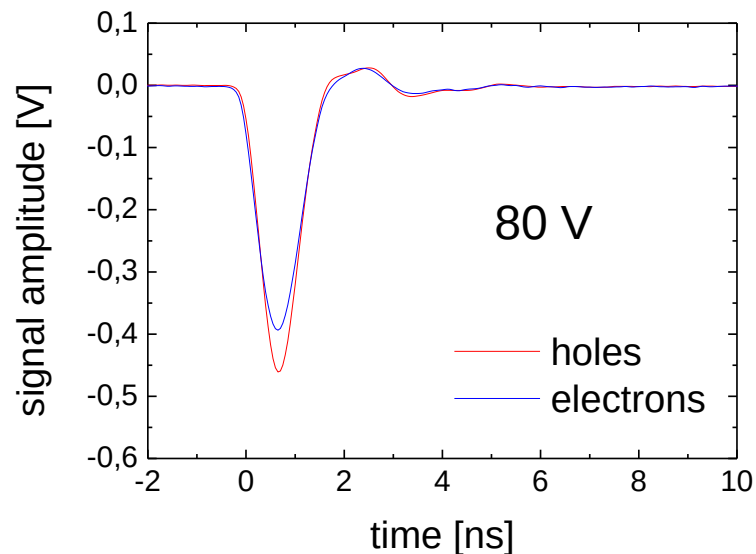
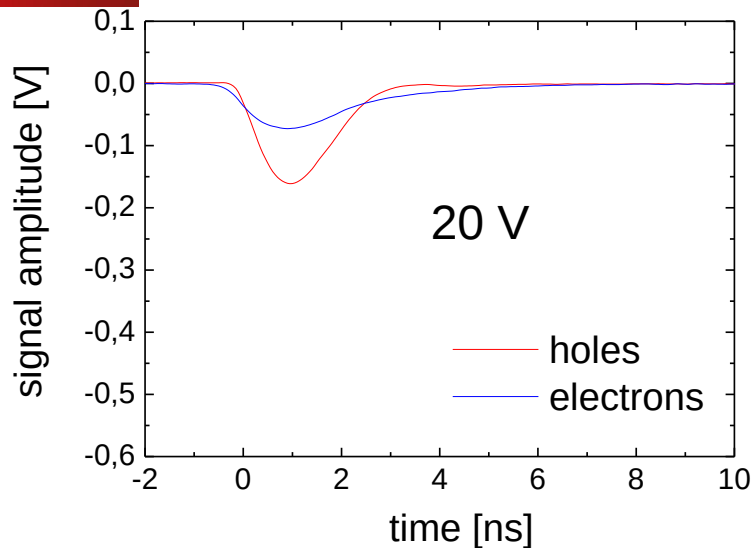
- CVIDEC C2 fast amplifier
- DSO as DAQ

cividec
Instrumentation



- fast rise and decay times – nice time detector
- no de-trapping visible
- no flat top, high amplitude (built-in field)
- drift velocity seems faster than CVD
(but thin sample, internal field → need tct on thicker samples)

TCT – NDT6



puzzling: no de-trapping visible

(Very) Preliminary characteristics of lia HPHT samples from NDT were performed:

Only two samples out of six give promising results

I-V: majority of the samples are conductive (impossible to apply bias)

- some of them have acceptable level of leakage current
- rarely samples are highly resistive

CCE: - for holes drift reaches 100%; for electrons drift reaches 80%

- stable operation for holes drift, with spectroscopic quality

deep trapping for electrons leads to polarization, shallow trapping for holes all charge released @ RT within shaping time used (3micros)

TCT: - fast signals including rise and decay time (no slow component)

- holes faster than electrons, drift velocity seems higher than CVD

In current state NDT samples can be used for some detector applications (if same or better quality than NDT6): eg. traversing particles, time measurements, tagging, spectroscopy with majority of holes drift

Thank you very much for your kind attention !



Commissariat à l'énergie atomique et aux énergies alternatives
Institut List | CEA SACLAY NANO-INNOV | BAT. 861 – PC142
91191 Gif-sur-Yvette Cedex - FRANCE
www-list.cea.fr

Établissement public à caractère industriel et commercial | RCS Paris B 775 685 019

NOT 2

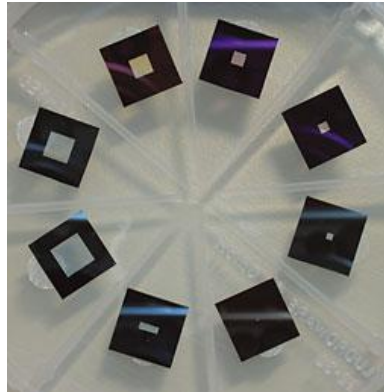
0 - 8 pA
-10V - 6.7 nA
-20V - 41 nA
-30V - 180 nA
-40V - 270 nA
-50V - 670 nA
-60V - 1.36 μ A
-70V - 2.9 μ A
-80V - 6.4 μ A
-90V - 20 μ A
-100V - 53 μ A

NOT 2. 57 μ m

0V $\rightarrow$ 0.01 pA
+10V $\rightarrow$ 0.05 pA
+20V $\rightarrow$ 0.05 pA
+50V $\rightarrow$ 0.3 pA
+80V $\rightarrow$ 3 pA
+150V $\rightarrow$ 32 pA
+180V $\rightarrow$ 57 pA
+200V $\rightarrow$ breakdown ?

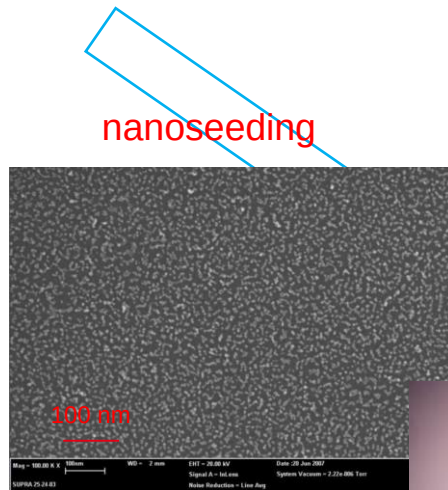
-10V $\rightarrow$ 0.01 pA
-20V $\rightarrow$ 0.04 pA
-30V $\rightarrow$ 0.5 pA
-80V $\rightarrow$ -2 pA
-150V $\rightarrow$ -15 pA
-180V $\rightarrow$ -37 pA
-200V $\rightarrow$ -54 pA
-220V $\rightarrow$ -84 pA
-240V $\rightarrow$ -135 pA
-260V $\rightarrow$ -241 pA
-300V $\rightarrow$ -1 nA
-320V $\rightarrow$ -2.4 nA
-360V $\rightarrow$ -5 nA $\uparrow$
-400V $\rightarrow$ -6 nA $\uparrow$
-450V $\rightarrow$ -6.7 nA $\uparrow$
-500V $\rightarrow$ -7 nA $\uparrow$

BNCD SEE MEMBRANES



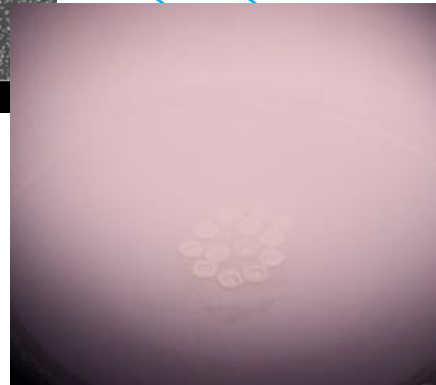
Silicon nitride windows

- commercial product
- not expensive
- 150 nm thick membrane

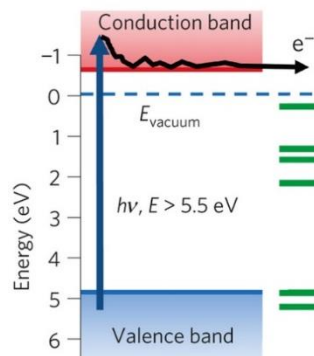


nanoseeding

CVD growth

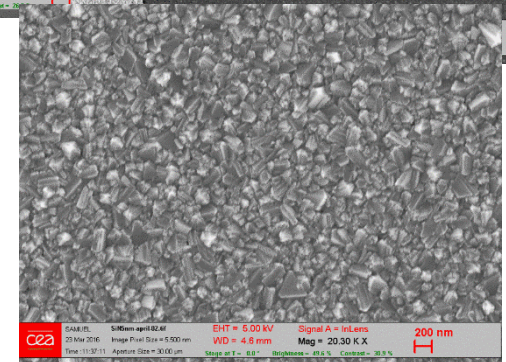
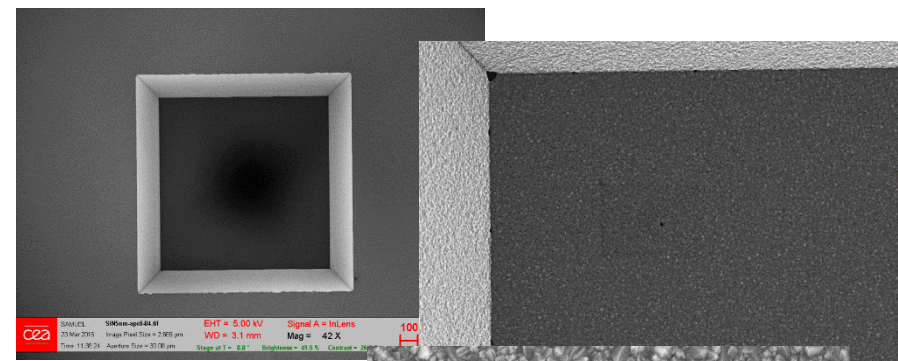


- seeding with diamond nanoparticles 5-20nm in PDDAC

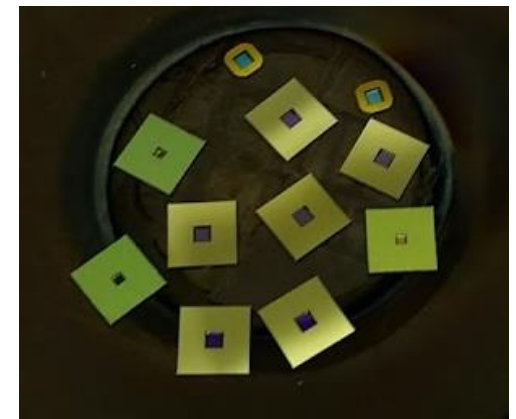


NEA

- MFCVD diamond growth (H_2/CH_4)
- temperature ~ 500-800 C
- boron doping (TMP) up to metallic conductivity
- few hours processing



BNCD coated silicon nitride windows



measured values a wish list

Table 1. Important properties of diamond for high energy physics applications [2]

Property	Silicon	Diamond	Effect in Diamond
Band gap [eV]	1.12	5.45	Leakage current is very small and No cooling required
Electron mobility [$\text{cm}^2/\text{V}\cdot\text{sec}$]	1450	2200	Signal is very fast
Hole mobility [$\text{cm}^2/\text{V}\cdot\text{sec}$]	500	1600	
Dielectric constant	11.9	5.7	Low Capacitance and noise
Atomic displacement energy [eV]	21	43	Radiation hardness is high
Electron-hole pair creation energy [eV]	3.6	13.6	Smaller signal
Mean electron-hole pair by MIP (Minimum Ionizing Particle) in $1 \mu\text{m}$	89	36	Smaller signal
Charge collection efficiency (%)	100 (Single crystal)	100% for Single Crystal & 50% for Polycrystalline	Smaller signal
Thermal conductivity [$\text{W}/\text{cm}\cdot\text{K}$]	1.5	22	No c

diamond as a solid-state ionization chamber

